

Customer No. 22,852
Attorney Docket No. 04329.3299

that the cited documents do not constitute "prior art" under United States law, applicants reserve the right to present to the Office the relevant facts and law regarding the appropriate status of such documents. Applicants further reserve the right to take appropriate action to establish the patentability of the disclosed invention over the listed documents, should one or more of the documents be applied against the claims of the present application.

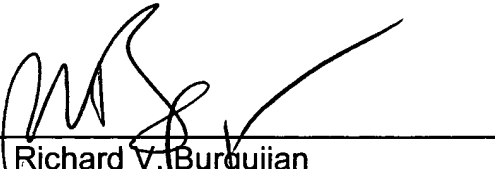
If there is any fee due in connection with the filing of this Statement, please charge the fee to our Deposit Account No. 06-0916.

Respectfully submitted,

FINNEGAN, HENDERSON, FARABOW,
GARRETT & DUNNER, L.L.P.

Dated: August 19, 2004

By: _____


Richard V. Burgujian
Reg. No. 31,744

Enclosures
RVB/FPD/blc



INFORMATION DISCLOSURE CITATION

Atty. Docket No.	04329.3299	Application No.	10/820,182
Applicants	Tsutomu SATO et al.		
Filing Date	April 8, 2004	Group:	2811

U.S. PATENT DOCUMENTS

Examiner Initial*	Document Number	Issue Date	Name	Class	Sub Class	Filing Date If Appropriate

FOREIGN PATENT DOCUMENTS

Document Number	Publication Date	Country	Class	Sub Class	Translation Yes or No

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

	Sato et al., "A NEW SUBSTRATE ENGINEERING FOR THE FORMATION OF EMPTY SPACE IN SILICON (ESS) INDUCED BY SILICON SURFACE MIGRATION", International Electron Device Meeting, pps. 20.6.1-20.6.4, (1999).
	Sato et al., "FABRICATION OF SILICON-ON-NOTHING STRUCTURE BY SUBSTRATE ENGINEERING USING THE EMPTY-SPACE-IN-SILICON FORMATION TECHNIQUE", Japanese Journal of Applied Physics, Vol. 43, pps. 12-18, (2004).

Examiner	Date Considered
*Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	
Form PTO 1449	Patent and Trademark Office - U.S. Department of Commerce